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PATENT

Sheet 1 of 1

FORM PTO-1449 (Modified)  
(Rev. 7-80)

U.S. Dept. of Commerce  
Patent and Trademark Office

Atty Docket No.  
SCP-6620 ()

Appln. No.  
09/408,279

INFORMATION DISCLOSURE CITATION

Applicant(s)  
JOHN J. ROSATO ET AL.

Filing Date  
September 29, 1999

Group  
1751

(Use several sheets if necessary)

U.S. PATENT DOCUMENTS

*Examiner Initials		Document Number	Date	Name	Class	Subclass	Filing Date
ME	AA	5,175,124	12/29/92	Winebarger	437	180	3/25/91
ME	AB	5,102,777	4/7/92	Lin et al.	430	331	2/1/90

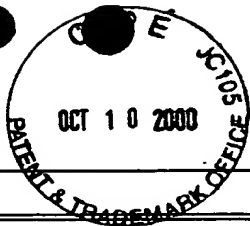
FOREIGN PATENT DOCUMENTS

*Examiner Initials		Document Number	Date	Country	Class	Subclass	Translation YES NO
ME	AC	EP0867924A2	9/30/96	Europe	H01L21	306	yes
	AD	EL0784336A2	7/16/97	Europe	H01L21	00	yes
	AE	EP0849772A1	6/24/98	Europe	H01L-21	00	yes
	AD	EP0596515B1	10/1/97	Europe	G03F7	42	yes
	AG	EP0817246A1	1/7/98	Europe	H01L21	00	yes
	AH	EP0874387A1	10/28/97	Europe	H01L21	00	yes
	AI	EP0649168A2	10/18/94	Europe	H01L21	306	yes
	AJ	EP0501492A2	2/27/92	Europe	H01L21	306	yes
	AK	EP0560324B1	8/19/98	Europe	C11D/	39	yes
ME	AL	EP678788A2	4/13/95	Europe	G03F7	42	yes

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ME	AM	G. Schwartzkopf - Design of Low Alkalinity Organic Photoresist Strippers, Proceedings of the Symposia On Interconnects, Contact Metallization and Multilevel Metallization 1993.
	AN	M.M. Heynes et al. - Advanced Cleaning and Ultra-Thin Oxide Technology. Date Unknown
	AO	Rita Vos et al. A Novel Environmentally Friendly Corrosion-Free Post Stripping Rinsing Procedure After Solvent Strip. June 10-12, 1997 - Kyoto - 1997 Symposium on VLSI Technology
	AP	O.J. Antilila et al. Effect of Chemicals on Metal Contamination on Silicon Wafers. April 1992, Vol. 139 No. 4 - Journal of Electrochemical Society
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	AR	Stanley Wolf, Ph.D. - Silicon Processing for the VLSI Era - Volume 1, Process Technology, Chapter 15 Wet Processing: Cleaning, Etching and Liff-off - 1986

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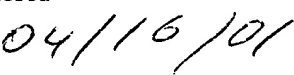


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Examiner <i>crf</i>	Date Considered <i>04/16/2001</i>
<small>* Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>	

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<b>INFORMATION DISCLOSURE CITATION</b>  (Use several sheets if necessary)				Applicant(s) JOHN J.ROSATO ET AL.			
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	AB						
FOREIGN PATENT DOCUMENTS							
*Examiner Initials		Document Number	Date	Country	Class	Subclass	Translation YES NO
MC	AC	EP0846985A1	10/6/98	Europe	G03F	7/42	yes
OTHER DOCUMENTS							
	AD						
Examiner				Date Considered			
							
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